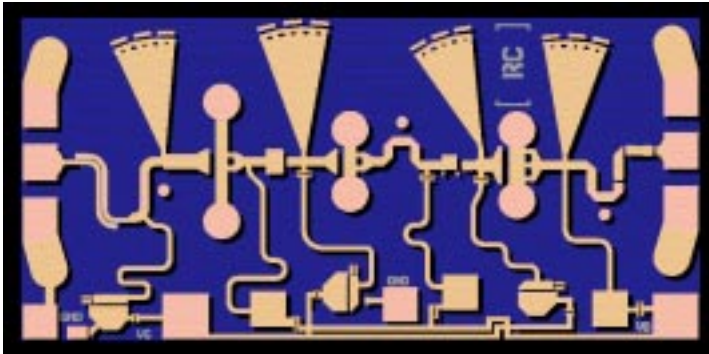


**60GHz Low Noise Amplifier**

**TGA4600-EPU**

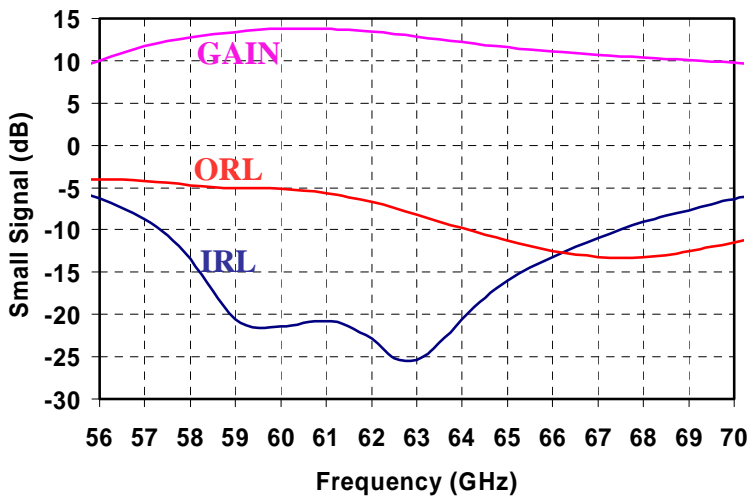


**Key Features**

- Typical Frequency Range: 57 - 65 GHz
- 4 dB Nominal Noise Figure
- 13 dB Nominal Gain
- Bias 3.0 V, 41 mA
- 0.15 um 3MI pHEMT Technology
- Chip Dimensions 1.62 x 0.84 x 0.10 mm (0.064 x 0.033 x 0.004 in)

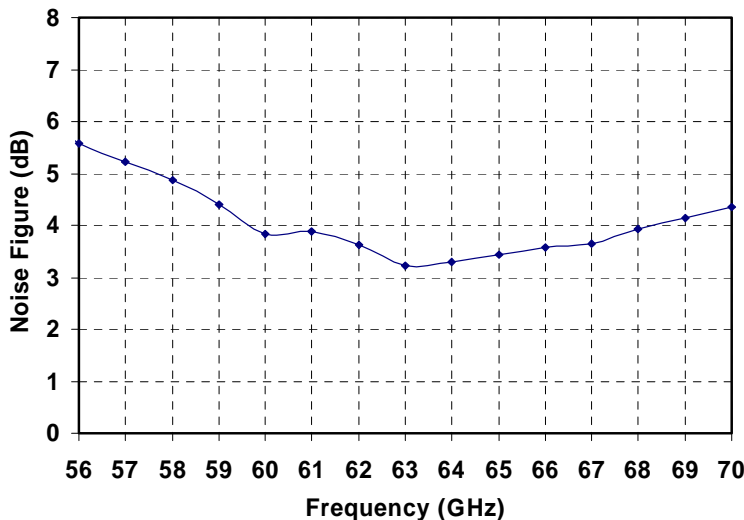
**RF Probe Data**

Bias Conditions: Vd = 3.0 V, Id = 41 mA



**Primary Applications**

- Wireless LAN
- Point-to-Point Radio



Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications are subject to change without notice

**TABLE I**  
**MAXIMUM RATINGS <sup>1/</sup>**

SYMBOL	PARAMETER	VALUE	NOTES
V <sub>d</sub>	Drain Voltage	5 V	<u>2/</u>
V <sub>g</sub>	Gate Voltage Range	-1 TO +0.5 V	
I <sub>d</sub>	Drain Current	200 mA	<u>2/ 3/</u>
I <sub>g</sub>	Gate Current	5 mA	<u>3/</u>
P <sub>IN</sub>	Input Continuous Wave Power	15 dBm	
P <sub>D</sub>	Power Dissipation	0.39W	<u>2/ 4/</u>
T <sub>CH</sub>	Operating Channel Temperature	150 °C	<u>5/ 6/</u>
T <sub>M</sub>	Mounting Temperature (30 Seconds)	320 °C	
T <sub>STG</sub>	Storage Temperature	-65 to 150 °C	

- 1/ These ratings represent the maximum operable values for this device.
- 2/ Combinations of supply voltage, supply current, input power, and output power shall not exceed P<sub>D</sub>.
- 3/ Total current for the entire MMIC.
- 4/ When operated at this bias condition with a base plate temperature of 70°C, the median life is 1.0E+6 hrs.
- 5/ Junction operating temperature will directly affect the device median time to failure (MTTF). For maximum life, it is recommended that junction temperatures be maintained at the lowest possible levels.
- 6/ These ratings apply to each individual FET.

**TABLE II**  
**DC PROBE TESTS**  
(T<sub>a</sub> = 25 °C, Nominal)

SYMBOL	PARAMETER	MIN.	TYP.	MAX.	UNITS
V <sub>BVGD, Q1-Q3</sub>	Breakdown Voltage Gate-Source	-30		-5	V
V <sub>BVGS, Q3</sub>	Breakdown Voltage Gate-Source	-30		-5	V
V <sub>P, Q1,2,3</sub>	Pinch-off Voltage	-1.0		-0.1	V

Q1 is 100 um FET, Q2 is 100 um FET, Q3 is 210 um FET.

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**TABLE III**  
**ELECTRICAL CHARACTERISTICS**

(Ta = 25 °C Nominal)

PARAMETER	TYPICAL	UNITS
Frequency Range	57 - 65	GHz
Drain Voltage, Vd	3.0	V
Drain Current, Id	41	mA
Gate Voltage, Vg	-0.5 - 0	V
Small Signal Gain, S21	13	dB
Input Return Loss, S11	20	dB
Output Return Loss, S22	6	dB
Noise Figure, NF	4	dB

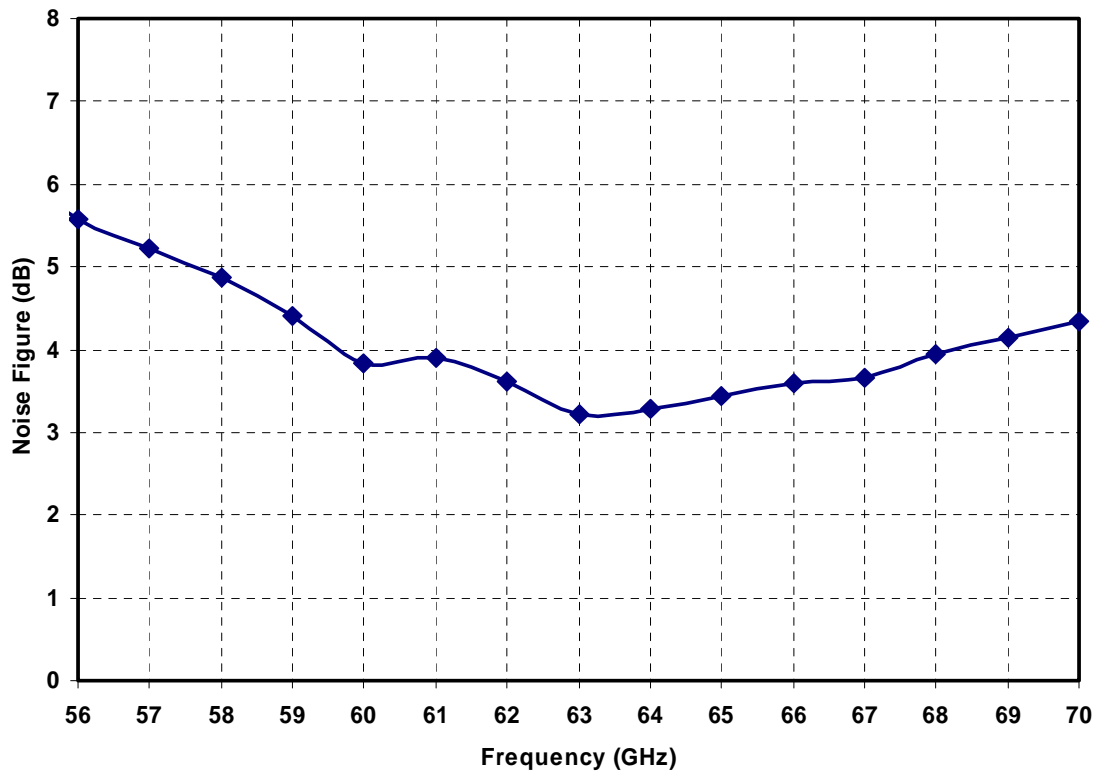
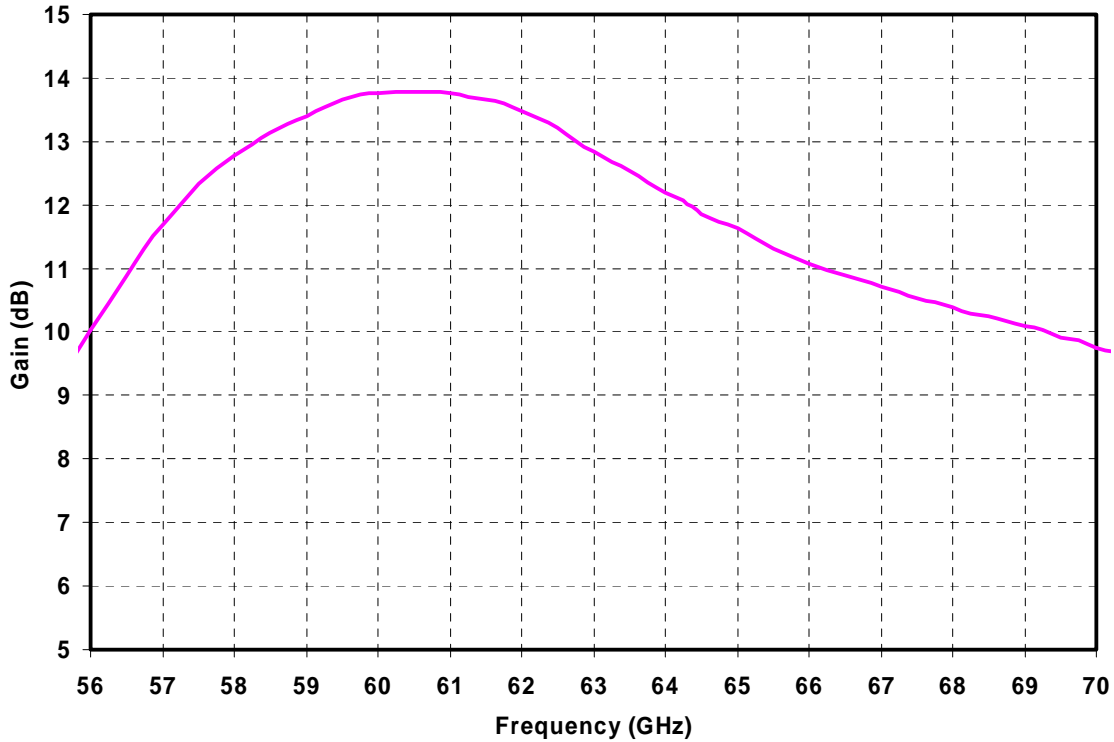
**TABLE IV**  
**THERMAL INFORMATION**

PARAMETER	TEST CONDITIONS	T <sub>CH</sub> (°C)	R <sub>θJC</sub> (°C/W)	T <sub>M</sub> (HRS)
R <sub>θJC</sub> Thermal Resistance (channel to Case)	Vd = 3 V Id = 41 mA P <sub>diss</sub> = 0.12 W	80	83	1.2 E+9

Note: Assumes eutectic attach using 1.5 mil 80/20 AuSn mounted to a 20 mil CuMo Carrier at 70°C baseplate temperature. Worst case condition with no RF applied, 100% of DC power is dissipated.

**RF Probe Data**

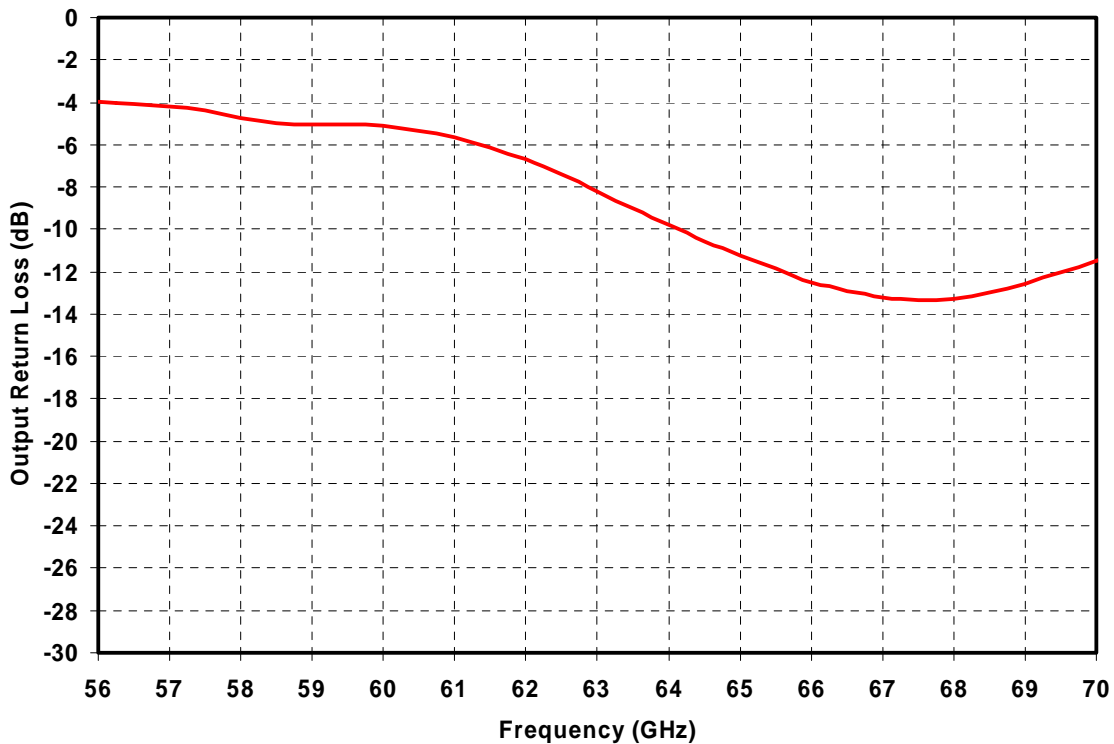
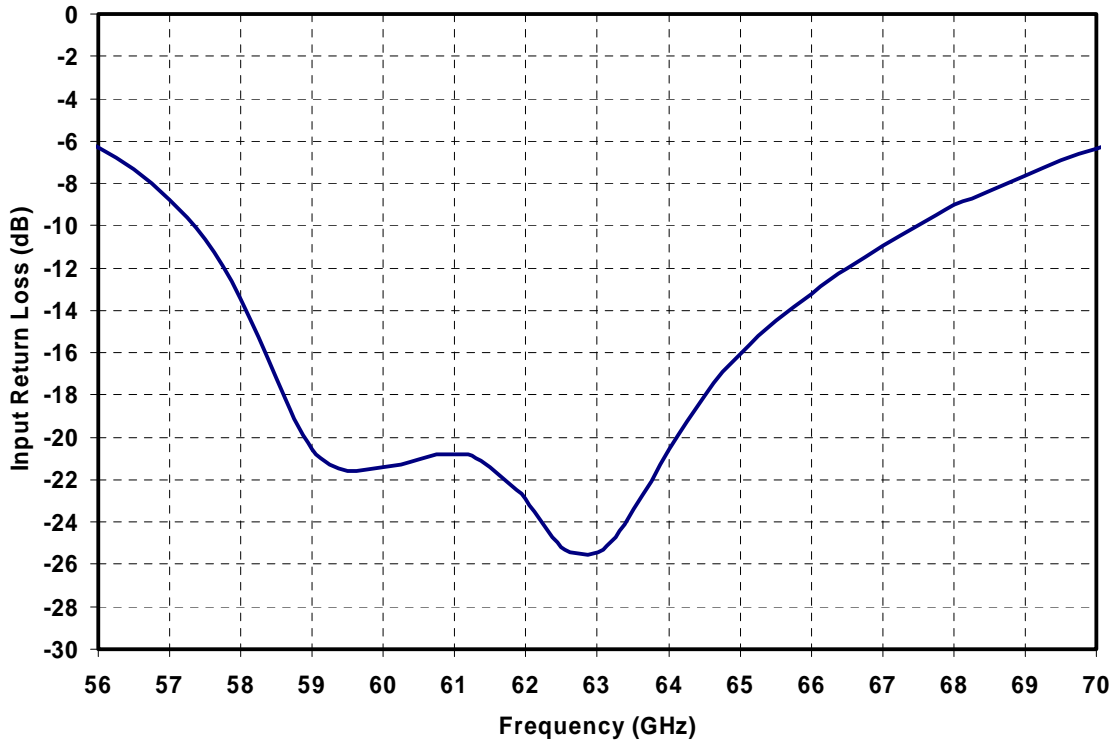
Bias Conditions:  $V_d = 3.0\text{ V}$ ,  $I_d = 41\text{ mA}$



Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications are subject to change without notice

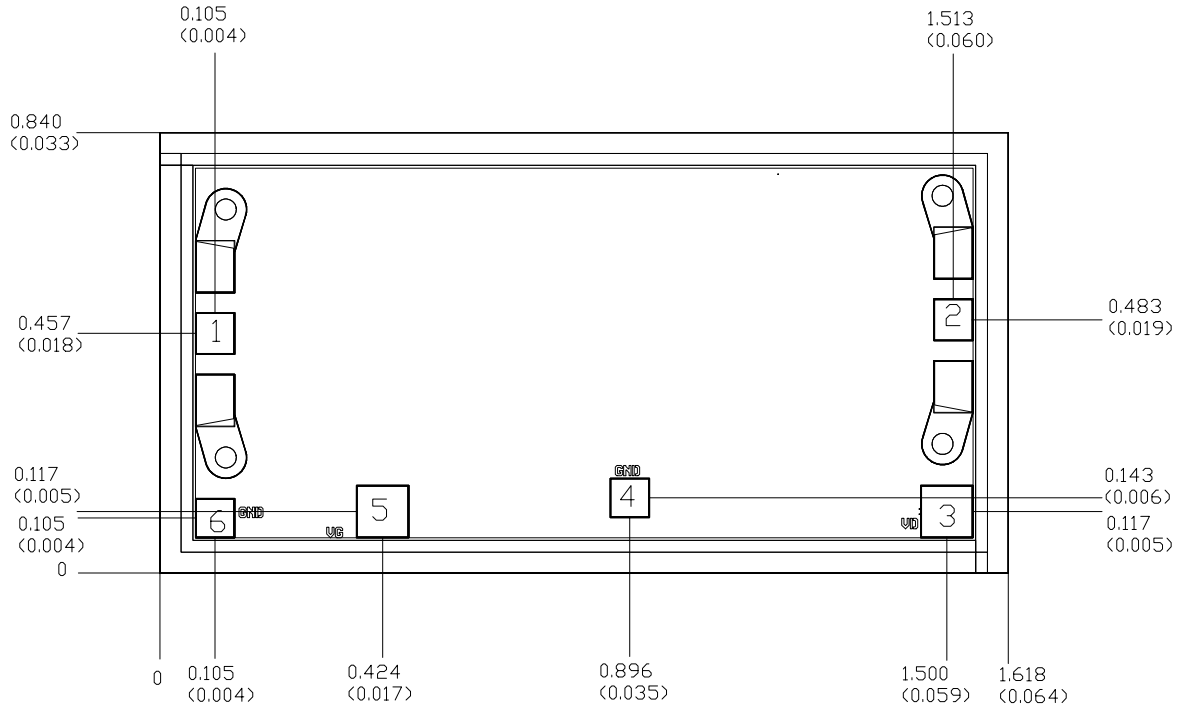
### RF Probe Data

Bias Conditions:  $V_d = 3.0\text{ V}$ ,  $I_d = 41\text{ mA}$



Note: Devices designated as EPU are typically early in their characterization process prior to finalizing all electrical and process specifications. Specifications are subject to change without notice

**Mechanical Drawing**



Units: Millimeters (inches)

Thickness: 0.050 (0.002) (reference only)

Chip edge to bond pad dimensions are shown to center of bond pad

Chip size tolerance: +/- 0.051 (0.002)

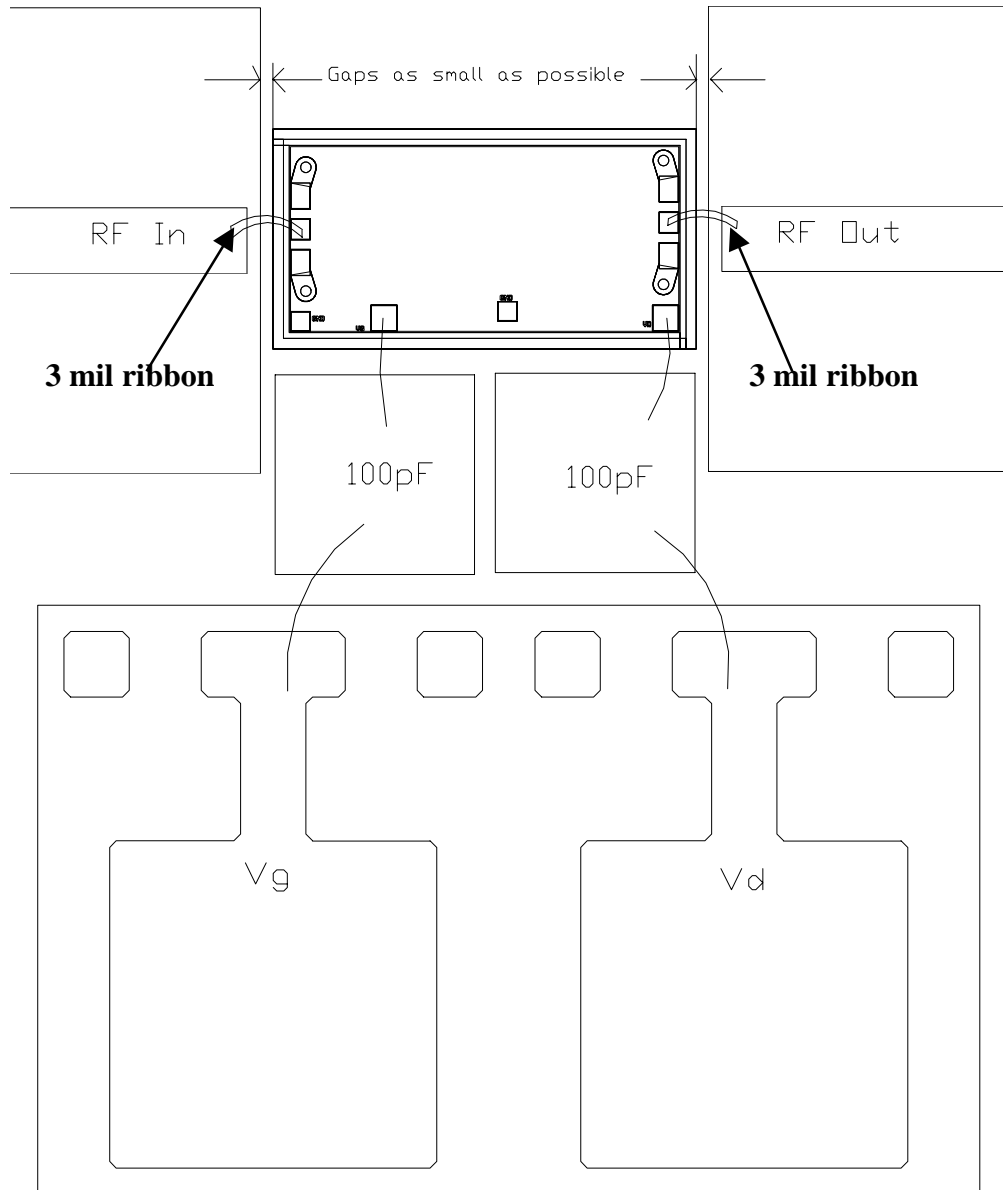
RF Ground is backside of MMIC

Bond pad #1:	(RF In)	0.075 x 0.080 (0.003 x 0.003)
Bond pad #2:	(RF Out)	0.075 x 0.080 (0.003 x 0.003)
Bond pad #3:	(Vd)	0.100 x 0.100 (0.004 x 0.004)
Bond pad #4 & #6:	(GND, N/C)	0.075 x 0.075 (0.003 x 0.003)
Bond pad #5:	(Vg)	0.100 x 0.100 (0.004 x 0.004)

**GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.**

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**Recommended Chip Assembly Diagram**



**Ribbons as short as possible**

**GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.**

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## **Assembly Process Notes**

Reflow process assembly notes:

- Use AuSn (80/20) solder with limited exposure to temperatures at or above 300<sup>0</sup>C (30 seconds max).
- An alloy station or conveyor furnace with reducing atmosphere should be used.
- No fluxes should be utilized.
- Coefficient of thermal expansion matching is critical for long-term reliability.
- Devices must be stored in a dry nitrogen atmosphere.

Component placement and adhesive attachment assembly notes:

- Vacuum pencils and/or vacuum collets are the preferred method of pick up.
- Air bridges must be avoided during placement.
- The force impact is critical during auto placement.
- Organic attachment can be used in low-power applications.
- Curing should be done in a convection oven; proper exhaust is a safety concern.
- Microwave or radiant curing should not be used because of differential heating.
- Coefficient of thermal expansion matching is critical.

Interconnect process assembly notes:

- Thermosonic ball bonding is the preferred interconnect technique.
- Force, time, and ultrasonics are critical parameters.
- Aluminum wire should not be used.
- Maximum stage temperature is 200<sup>0</sup>C.

***GaAs MMIC devices are susceptible to damage from Electrostatic Discharge. Proper precautions should be observed during handling, assembly and test.***

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